

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(Multiple sheets used when necessary)

SHEET 1 OF 1

Application No.	10/820,381
Filing Date	April 8, 2004
First Named Inventor	Plasterer, et al.
Art Unit	2819
Examiner	Anh Q. Tran
Attorney Docket No.	DATUMTE.018A

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U.S. PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
A-T		3,633,120	01-04-1972	Battjes	
		5,689,178	11-18-1997	Otake	
		5,808,513	09-15-1998	Archer	
		5,889,425	03-30-1999	Kimura	
		6,084,472	07-04-2000	Gilbert	
		6,111,445	08-29-2000	Zerbe	
A		6,433,595	08-13-2002	Tung	

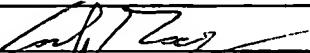
FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T ¹

NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ¹
A-T		BARRIE GILBERT, <i>The Multi-tanh Principle: A Tutorial Overview</i> , IEEE Journal of Solid-State Circuits, Vol. 33, No. 1, January 1998, Institute of Electrical and Electronics Engineers, Inc., pp. 2-17.	
A		BEHNAM AGHDAIE AND BING SHEU, <i>Overcoming Limitations of Lumped MOS Models</i> , Circuits & Devices, March 2000, pp 19-26	

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Examiner Signature		Date Considered	3/13/06
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*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

T¹ - Place a check mark in this area when an English language Translation is attached.